

REMARKS

Applicants thanks Examiner for their detailed review of the application. Examiner currently rejects claims 1-7, 9-21, and 23-24 under 35 U.S.C. 102(e) as being anticipated by U.S. Patent Application Publication No. 2005/0236714, herein referred to as Leu et al. Leu et al. discloses, in paragraph 15, examples of porogen and porous matrix pairings as follows:

Preferred pairings of matrix and porogen materials, for example, include but are not limited to: an oligomeric porogen, such as a low molecular weight polystyrene, grafted as a side chain onto a tetraethylorthosilicate ("TEOS") porous matrix polymer; crosslinked polyarylene matrix combined with polystyrene porogen; silicon dioxide matrix with polyethylene oxide porogen; silicon dioxide matrix with polynorbornene-based porogen such as that sold under the trade name "Unity.TM.400" by Promerus LLC; and CDO matrix with polyethylene or polyethylene oxide porogen.

However, Leu et al. does not suggest the use of a zeolite material as a porogen or the use of a zeolite-CDO composite film or interlayer dielectric. In fact Leu et al. references the use of a zeolite material in reference to second ILD layer 124. At paragraph 0024 Leu et al discloses, "a second ILD layer (124) is positioned between the first ILD layer (102) and the substrate layer (100)." In contrast, applicant's claim 1 discloses, "depositing a carbon doped oxide (CDO) in the zeolite film to form a zeolite - CDO composite film," not depositing Leu et al.'s matrix - porogen composite film on a zeolite ILD. In other words, applicant discloses a composite, while Leu et al. suggests deposition of separate zeolite and porogen film layers. Similarly claim 19 is directed at a CDO-zeolite composite ILD, not a first ILD stacked on a second zeolite ILD, as suggested by Leu et al.

In regards to Examiner's rejection of claims 8 and 22 under 35 U.S.C. 103(a), applicant's claims 8 and 22 depend from claims 1 and 19; therefore, applicant submits these claims are in condition for allowance for the reasons stated above. Furthermore, Applicants respectfully submit that other dependent claims 2-7, 9-18, 20-21, and 23-24 are now in condition for allowance for the reasons stated above.

If there are any additional charges, please charge Deposit Account No. 50-0221. If a another telephone interview would in any way expedite the prosecution of the present application , the Examiner is invited to contact David P. McAbee at (503) 712-4988.

Respectfully submitted,
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